



Docket No.: 6301/Consilium/DV

#8/11-4-02
PATENT/OFFICIAL

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Badri N. KRISHNAMURTHY et al.

Serial No. 09/928,474

Filed: August 14, 2001

For: EXPERIMENT MANAGEMENT SYSTEM, METHOD AND MEDIUM

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Group Art Unit: 2171

Examiner:

RECEIVED
OCT -4 2002
TECHNOLOGY CENTER 2800

RECEIVED
SEP 20 2002
Technology Center 2100

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
Washington, D.C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right

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to present to the Office the relevant facts and law regarding the appropriate status of such document.

No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,


HALE AND DORR LLP

A handwritten signature in black ink, appearing to read "Scott M. Alter", is written over the printed name.

Scott M. Alter

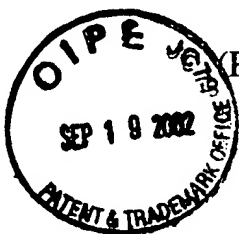
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Date: 9/19/02

INFORMATION DISCLOSURE CITATION IN AN APPLICATION  (PTO-1449)				ATTY. DOCKET NO. 6301/Consilium/DV		SERIAL NO. 09/928,474 RECEIVED SEP 20 2002	
				APPLICANT Badri N. KRISHNAMURTHY et al.			
				Technology Center 2100			
FILING DATE August 14, 2001				GROUP 2171			
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
	4,698,766	10/06/87	Entwistle et al.			05/17/85	
	4,967,381	10/30/90	Lane et al.			07/06/89	
	5,208,765	05/04/93	Turnbull			07/20/90	
	5,226,118	07/06/93	Baker et al.			01/29/91	
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FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	61-171147	08/01/86	Japan				X
	6-184434	07/05/94	Japan				X
	0 621 522 A2	10/26/94	Europe			X	
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
	February 1984. "Method and Apparatus of in Situ Measurement and Overlay Error Analysis for Correcting Step and Repeat Lithographic Cameras." <i>IBM Technical Disclosure Bulletin</i> , pp. 4855-4859.						
	October 1984. "Method to Characterize the Stability of a Step and Repeat Lithographic System." <i>IBM Technical Disclosure Bulletin</i> , pp. 2857-2860.						
EXAMINER				DATE CONSIDERED			

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

**INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION**



(PTO-1449)

ATTY. DOCKET NO.
6301/Consilium/DV

SERIAL NO.
09/928,474

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SEP 20 2002

Technology Center 2171

APPLICANT
Badri N. KRISHNAMURTHY et al.

FILING DATE
August 14, 2001

GROUP
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						Yes	No
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	10-173029	06/26/98	Japan				X
	0 895 145 A1	02/03/99	Europe			X	
	11-126816	05/11/99	Japan				X

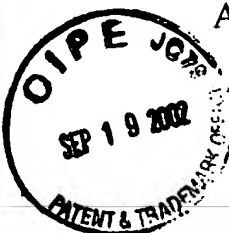
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	Schmid, Hans Albrecht. 1995. "Creating the Architecture of a Manufacturing Framework by Design Patterns." Austin, Texas: OOPSLA.
	Baliga, John. July 1999. "Advanced Process Control: Soon to be a Must." Cahners Semiconductor International. www.semiconductor.net/semiconductor/issues/issues/1999/jul99/docs/feature1.asp
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 6301/Consilium/DV		SERIAL NO. 09/928,474 <div style="text-align: center; border: 1px solid black; padding: 5px;"> RECEIVED SEP 20 2002 </div>	
				APPLICANT Badri N. KRISHNAMURTHY et al. Technology Center 2100			
				FILING DATE August 14, 2001		GROUP 2171	
U.S. PATENT DOCUMENTS							
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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	11-135601	05/21/99	Japan				X
	WO 00/05759	02/03/00	WO			X	
	WO 00/35063	06/15/00	WO			X	
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INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 6301/Consilium/DV		SERIAL NO. 09/928,474 RECEIVED SEP 20 2002 Technology Center 2100	
				APPLICANT Badri N. KRISHNAMURTHY et al.			
				FILING DATE August 14, 2001		GROUP 2171	
U.S. PATENT DOCUMENTS							
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	6,345,315	02/05/02	Mishra			08/12/98	
	6,366,934	04/02/02	Cheng et al.			06/02/99	
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	WO 00/79355 A1	12/28/00	WO			X	
	2001-76982	03/23/01	Japan				X
	WO 01/33501 A1	05/10/01	WO			X	
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
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